

L Number	Hits	Search Text	DB	Time stamp
10	400	laser and lens and source and (target wafer sample specimen) and gimbal	USPAT; EPO; JPO; DERWENT	2003/11/10 14:08
11	4	(((((laser and lens and source and (target wafer sample specimen)) and mecha\$6) and pivot) and ((lateral and vertical) (x and y))) and rota\$6) and energy with detect\$6 and gimbal	USPAT; EPO; JPO; DERWENT	2003/11/10 14:27
13	93	(((((laser and lens and source and (target wafer sample specimen)) and mecha\$6) and pivot) and ((lateral and vertical) (x and y))) and rota\$6) and energy with detect\$6	USPAT; EPO; JPO; DERWENT	2003/11/10 14:32
14	2	(((((laser and lens and source and (target wafer sample specimen)) and mecha\$6) and pivot) and ((lateral and vertical) (x and y))) and rota\$6) and energy with detect\$6) and detection adj cell	USPAT; EPO; JPO; DERWENT	2003/11/10 14:29
15	71	(laser and lens and source and (target wafer sample specimen)) and energy and detection adj cell	USPAT; EPO; JPO; DERWENT	2003/11/10 14:33
-	30269	laser and lens and source and (target wafer sample specimen)	USPAT; EPO; JPO; DERWENT	2003/11/10 14:08
-	0	(laser and lens and source and (target wafer sample specimen)) and energy adj desorption adj cell	USPAT; EPO; JPO; DERWENT	2003/11/07 08:31
-	1	(laser and lens and source and (target wafer sample specimen)) and energy adj detection adj cell	USPAT; EPO; JPO; DERWENT	2003/11/07 08:31
-	18446	(laser and lens and source and (target wafer sample specimen)) and mecha\$6	USPAT; EPO; JPO; DERWENT	2003/11/07 08:33
-	1349	((laser and lens and source and (target wafer sample specimen)) and mecha\$6) and pivot	USPAT; EPO; JPO; DERWENT	2003/11/07 08:33
-	790	((laser and lens and source and (target wafer sample specimen)) and mecha\$6) and pivot) and ((lateral and vertical) (x and y))	USPAT; EPO; JPO; DERWENT	2003/11/07 08:43
-	731	(((((laser and lens and source and (target wafer sample specimen)) and mecha\$6) and pivot) and ((lateral and vertical) (x and y))) and rota\$6	USPAT; EPO; JPO; DERWENT	2003/11/07 08:34
-	93	(((((laser and lens and source and (target wafer sample specimen)) and mecha\$6) and pivot) and ((lateral and vertical) (x and y))) and rota\$6) and energy with detect\$6	USPAT; EPO; JPO; DERWENT	2003/11/10 14:08
-	3140	(laser and lens and source and (target wafer sample specimen)) and ((mov\$5 and mecha\$6) same source)	USPAT; EPO; JPO; DERWENT	2003/11/07 08:43
-	1803	((laser and lens and source and (target wafer sample specimen)) and ((mov\$5 and mecha\$6) same source)) and ((lateral and vertical) (x and y))	USPAT; EPO; JPO; DERWENT	2003/11/07 09:21
-	853	((laser and lens and source and (target wafer sample specimen)) and ((mov\$5 and mecha\$6) same source)) and ((lateral and vertical) (x and y)) and rota\$6 same source	USPAT; EPO; JPO; DERWENT	2003/11/07 08:44
-	200	((laser and lens and source and (target wafer sample specimen)) and ((mov\$5 and mecha\$6) same source)) and ((lateral and vertical) (x and y)) and rota\$6 same source) and 250/\$ cels	USPAT; EPO; JPO; DERWENT	2003/11/07 09:17
-	1996	(pivot\$5 and rota\$5 and mov\$6) same laser	USPAT; EPO; JPO; DERWENT	2003/11/07 13:38
-	858	((pivot\$5 and rota\$5 and mov\$6) same laser) and (optic\$5 lens) and (target wafer sample specimen substrate)	USPAT; EPO; JPO; DERWENT	2003/11/07 09:18
-	849	((pivot\$5 and rota\$5 and mov\$6) same laser) and ((lateral and vertical) (x and y))	USPAT; EPO; JPO; DERWENT	2003/11/07 09:21
-	510	((pivot\$5 and rota\$5 and mov\$6) same laser) and ((lateral and vertical) (x and y) same source)	USPAT; EPO; JPO; DERWENT	2003/11/07 09:35

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-	328	((pivot\$5 and rotat\$5 and mov\$6) same laser) and ((lateral and vertical) (x and y) same source)) and lens	USPAT; EPO, JPO, DERWENT	2003/11/07 13:32
-	3	((pivot\$5 and rotat\$5 and mov\$6) same laser) and ((lateral and vertical) (x and y) same source)) and lens) and virtual adj source	USPAT; EPO, JPO; DERWENT	2003/11/07 13:34
-	1	((pivot\$5 and rotat\$5 and mov\$6) same laser) and ((lateral and vertical) (x and y) same source)) and lens) and detection adj cell	USPAT; EPO, JPO; DERWENT	2003/11/07 13:33
-	77	(laser and lens and source and (target wafer sample specimen)) and virtual adj source	USPAT; EPO, JPO; DERWENT	2003/11/07 13:35
-	4	((pivot\$5 and rotat\$5 and mov\$6) same laser) and virtual adj source	USPAT; EPO, JPO; DERWENT	2003/11/07 13:36
-	0	((pivot\$5 and rotat\$5 and mov\$6) same laser) and laser adj desorption adj spectrometer	USPAT; EPO, JPO; DERWENT	2003/11/07 13:36
-	0	laser adj desorption adj spectrometer	USPAT; EPO, JPO; DERWENT	2003/11/07 13:36
-	372	laser adj desorption with spectrometer	USPAT; EPO, JPO; DERWENT	2003/11/07 13:37
-	6370	((pivot\$5 and rotat\$5 and mov\$6) same laser) adn (laser adj desorption with spectrometer)	USPAT; EPO, JPO; DERWENT	2003/11/07 13:37
-	1	((pivot\$5 and rotat\$5 and mov\$6) same laser) and (laser adj desorption with spectrometer)	USPAT; EPO, JPO; DERWENT	2003/11/07 13:37
-	8	(laser and (target wafer substrate specimen sample) and detection adj cell and lens) and virtual	USPAT; EPO, JPO; DERWENT	2003/11/07 13:41
-	1	(laser and (target wafer substrate specimen sample) and detection adj cell and lens) and virtual adj source	USPAT; EPO, JPO; DERWENT	2003/11/07 13:41
-	154	laser and (target wafer substrate specimen sample) and detection adj cell and lens	USPAT; EPO, JPO; DERWENT	2003/11/07 14:29